

Refine Search

Search Results -

Terms	Documents
L3 and 204/\$.ccls.	43

Database:

US Pre-Grant Publication Full-Text Database
 US Patents Full-Text Database
 US OCR Full-Text Database
 EPO Abstracts Database
 JPO Abstracts Database
 Derwent World Patents Index
 IBM Technical Disclosure Bulletins

Search:

L4

Refine Search

Recall Text

Clear

Interrupt

Search History

DATE: Friday, August 05, 2005 [Printable Copy](#) [Create Case](#)

Set Name Query

side by side

Hit Count Set Name

result set

DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=OR

<u>L4</u>	L3 and 204/\$.ccls.	43	<u>L4</u>
<u>L3</u>	L2 and (inert adj gas)	100	<u>L3</u>
<u>L2</u>	L1 and target	154	<u>L2</u>
<u>L1</u>	magnetron and cathode and sputter\$2 and nozzle and gas and argon	179	<u>L1</u>

END OF SEARCH HISTORY